

Myungjun Lee

List of Publications by Year in descending order

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Version: 2024-02-01

21
papers

237
citations

1163117

8
h-index

1125743

13
g-index

21
all docs

21
docs citations

21
times ranked

231
citing authors

#	ARTICLE	IF	CITATIONS
1	Field-portable reflection and transmission microscopy based on lensless holography. Biomedical Optics Express, 2011, 2, 2721.	2.9	106
2	Modern Trends in Imaging VIII: Lensfree Computational Microscopy Tools for Cell and Tissue Imaging at the Point-of-Care and in Low-Resource Settings. Analytical Cellular Pathology, 2012, 35, 229-247.	1.4	21
3	Microsphere-assisted, nanospot, non-destructive metrology for semiconductor devices. Light: Science and Applications, 2022, 11, 32.	16.6	19
4	Improved slow-light delay performance of a broadband stimulated Brillouin scattering system using fiber Bragg gratings. Applied Optics, 2008, 47, 6404.	2.1	18
5	High-fidelity, broadband stimulated-Brillouin-scattering-based slow light using fast noise modulation. Optics Express, 2011, 19, 687.	3.4	17
6	SBS gain-based slow-light system with a Fabry-Pérot resonator. Optics Communications, 2008, 281, 2975-2984.	2.1	12
7	Information theoretic framework for the analysis of a slow-light delay device. Journal of the Optical Society of America B: Optical Physics, 2008, 25, C31.	2.1	10
8	Information-theoretic analysis of a stimulated-Brillouin-scattering-based slow-light system. Applied Optics, 2011, 50, 6063.	2.1	8
9	Systematic design study of an all-optical delay line based on Brillouin scattering enhanced cascade coupled ring resonators. Journal of Optics (United Kingdom), 2010, 12, 104012.	2.2	5
10	Toward realization of high-throughput hyperspectral imaging technique for semiconductor device metrology. Journal of Micro-nanopatterning, Materials, and Metrology, 2022, 21, .	0.8	5
11	Lithography aware overlay metrology target design method. , 2016, , .		4
12	Capacity of electromagnetic communication modes in a noise-limited optical system. Applied Optics, 2016, 55, 1333.	2.1	4
13	Improving SEM image quality using pixel super resolution technique. Proceedings of SPIE, 2014, , .	0.8	2
14	A breakthrough on throughput and accuracy limitation in ellipsometry using self-interference holographic analysis. , 2021, , .		2
15	A new approach in optical metrology with multi-angle information through self-interferometric ellipsometry. , 2021, , .		2
16	Highly sensitive focus monitoring technique based on illumination and target co-optimization. , 2016, , .		1
17	Metrology target design (MTD) solution for diagonally orientated DRAM layer. Proceedings of SPIE, 2016, , .	0.8	1
18	Enhanced slow-light effect by combining broadband SBS system and off-resonance FBG. , 2008, , .		0

#	ARTICLE	IF	CITATIONS
19	Quantifying imaging performance bounds of extreme dipole illumination in high NA optical lithography. Proceedings of SPIE, 2016, , .	0.8	0
20	Microsphere-assisted ultra-small spot spectral reflectometry technique for semiconductor device metrology. , 2021, , .		0
21	Process resilient overlay target designs for advanced memory manufacture. , 2017, , .		0